

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S2	3368	lateral\$2 near2 etch\$3	US-PGPUB; USPAT	OR	OFF	2004/11/08 13:30
S3	538805	recess\$3	US-PGPUB; USPAT	OR	OFF	2004/11/08 13:30
S4	1619	438/424,435,437.ccls.	US-PGPUB; USPAT	OR	OFF	2004/11/08 13:31
S5	625	438/424,435,437.ccls. and ((lateral\$2 near2 etch\$3 ) or recess\$3)	US-PGPUB; USPAT	OR	OFF	2004/11/08 13:32
S18	321	438/437.ccls.	US-PGPUB; USPAT	OR	OFF	2004/11/09 22:04
S19	1143	oxide near liner	US-PGPUB; USPAT	OR	OFF	2004/11/09 22:05
S20	2065	atomic adj layer\$2 adj deposit\$3	US-PGPUB; USPAT	OR	OFF	2004/11/09 22:06
S21	1	S18 and (S19 same S20)	US-PGPUB; USPAT	OR	OFF	2004/11/09 22:13
S22	81553	chemical adj vapor adj deposit\$3	US-PGPUB; USPAT	OR	OFF	2004/11/09 22:13
S23	80848	cvd	US-PGPUB; USPAT	OR	OFF	2004/11/09 22:13
S24	36	S18 and (S19 same (S22 or S23))	US-PGPUB; USPAT	OR	OFF	2004/11/09 22:32
S25	13755	trench near isolation	US-PGPUB; USPAT	OR	OFF	2004/11/09 22:32
S26	279	S25 and (S19 same (S20 or S22 or S23))	US-PGPUB; USPAT	OR	OFF	2004/11/09 22:33